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THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): TAKAHASHI, et al.
Serial No.: 09/414,520
Filed: October 8, 1999
For: PLASMA PROCESSING APPARATUS AND A PLASMA
PROCESSING METHOD
Group: 1763
Examiner: Zervigon, R.

A8B
6/5/01
MW

AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

June 1, 2001

Sir:

In response to the Office Action of February 26,
2001, please amend the application as follows:

IN THE CLAIMS

Please cancel Claims 3 and 8.

Please amend Claims 1, 4 - 6 and 9 - 10 as follows:

B'
Sub C1/

1. (twice amended) In a plasma processing apparatus having
a vacuum processing chamber, a sample table for mounting a
sample which is processed in said vacuum processing
chamber, and a plasma generation means, wherein a plasma
processing is carried out by generating a plasma in
response to introduction of a gas which contains at least
carbon and fluorine, and a gas species is generated which
contains carbon and fluorine according to a plasma